(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau

(43) International Publication Date
9 January 2014 (09.01.2014)

WIPO | PCT

(10) International Publication Number
WO 2014/006546 A2

(51) **International Patent Classification**: Not classified

(21) **International Application Number**:
PCT/IB2013/055273

(22) **International Filing Date**:
27 June 2013 (27.06.2013)

(25) **Filing Language**: English

(26) **Publication Language**: English

(30) **Priority Data**:
12175333.9 6 July 2012 (06.07.2012) EP

(71) **Applicant**: **BASF SE** [DE/DE]; 67056 Ludwigshafen (DE).

(71) **Applicant** *(for CY only)*: **BASF SCHWEIZ AG** [CH/CH]; Klybeckstrasse 141, CH-4057 Basel (CH).

(71) **Applicant** *(for MN only)*: **BASF (CHINA) COMPANY LIMITED** [CN/CN]; 300 Jiangxinsha Road, Shanghai 200137 (CN).

(72) **Inventor**: **REICHARDT, Robert**; T6 12, 68161 Mannheim (DE).

(72) **Inventor**: **LI, Yuzhuo** *(deceased)*.

(72) **Inventor**: **LAUTER, Michael**; Gontardstrasse 6, 68163 Mannheim (DE).

(74) **Common Representative**: **BASF SE**; 67056 Ludwigshafen (DE).

(81) **Designated States** *(unless otherwise indicated, for every kind of national protection available)*: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) **Designated States** *(unless otherwise indicated, for every kind of regional protection available)*: ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

Published:

— *without international search report and to be republished upon receipt of that report (Rule 48.2(g))*

WO 2014/006546 A2

(54) **Title**: A CHEMICAL MECHANICAL POLISHING (CMP) COMPOSITION COMPRISING A NON-IONIC SURFACTANT AND AN AROMATIC COMPOUND COMPRISING AT LEAST ONE ACID GROUP

(57) **Abstract**: A chemical mechanical polishing (CMP) composition (Q) comprising : (A) Inorganic particles, organic particles, or a mixture or composite thereof, wherein the particles are cocoon-shaped; (B) a non-ionic surfactant; (C) an aromatic compound comprising at least one acid group (Y), or a salt thereof; and (M) an aqueous medium.